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**LITHOGRAPHY EXPERTS TO DISCUSS THEIR WORK WITH
INVERSE LITHOGRAPHY TECHNOLOGY
AT SPIE ADVANCED LITHOGRAPHY 2008**

PALO ALTO, Calif.—Feb. 20, 2008—Leading lithography experts will gather at the 2008 SPIE Advanced Lithography Symposium next week in San Jose, Calif. to present results of their work with Luminescent Technologies' ground-breaking inverse lithography technology (ILT). ILT is the semiconductor industry's first mask synthesis solution to transition beyond the limitations of optical proximity correction (OPC) software. The annual conference brings together the world's leading practitioners of micro and nanolithography in an international discussion forum dedicated to new advances in lithography techniques.

On Thursday, February 28 at 3:00 p.m., technology experts from Texas Instruments' Lithography Development/Simulation Group will deliver a paper titled, "Inverse Lithography as a DFM Tool: Accelerating Design-Rule Development with Model-based Assist Feature Placement, Fast Optical Proximity Correction and Lithographic Hot Spot Detection."

On Thursday, February 28 at 6:00 p.m., technology experts from the R&D Division at Hynix Semiconductor will deliver a presentation titled, "Evaluation of Inverse Lithography Technology for 55-nm Node Memory Devices."

In addition to the third-party presentations, Luminescent's General Manager Lithography Products, Linyong (Leo) Pang, Ph.D. will present new ILT results in a talk on Wednesday, February 27 at 1:40 p.m. The presentation is titled "Validation of Inverse Lithography Technology (ILT) and its Adaptive SRAF at Advanced Technology Nodes." Luminescent will also host a poster session on Thursday, February 28 at 6:00 p.m. The session is titled "Validation and Application of a Mask Model for Inverse Lithography."

About Inverse Lithography Technology

Inverse Lithography Technology (ILT), developed by Luminescent, is the semiconductor industry's first mask synthesis solution to transition beyond the limitations of optical proximity correction (OPC) software. It is the only automated resolution enhancement technology (RET) that starts directly with the desired IC pattern on the wafer, explores the entire available optical lithography space by mathematical inversion, and ultimately delivers a manufacturable mask pattern that generates the maximum design fidelity with the broadest possible process window.

A new-generation RET solution, ILT fits seamlessly into existing tape-out flows and leverages current-generation 193-nm lithography equipment to pattern 45- and 32-nm IC designs.

About Luminescent Technologies, Inc.

Luminescent provides lithography technology to the semiconductor industry. The company's Inverse Lithography Technology (ILT) products turn design intent into production reality by improving on-wafer pattern fidelity, expanding process windows, and accelerating time-to-silicon. Luminescent is a privately held, venture-backed company based in Palo Alto, California. To learn more about Luminescent, please visit the company on the Internet at www.luminescent.com.